

METHOD OF PROCESSING SUBSTRATE, METHOD OF MANUFACTURING
SEMICONDUCTOR DEVICE, PROGRAM, AND SUBSTRATE PROCESSING

APPARATUS

ABSTRACT

A method according to the present invention includes: (a) a step for setting the supply amount of a modifier on the basis of a relationship between the supply amount of the modifier and the characteristic of saturated adsorption of a raw material to a substrate; and (b) a step for supplying the modifier to the substrate on the basis of the set supply amount.

Fig. 4